MATERIALS AND METHODS FOR IMPRINT LITHOGRAPHY

ABSTRACT OF THE DISCLOSURE

[0042] One embodiment of the present invention relates to an imprinting material for imprint lithography that includes the surfactant $3M^{\text{M}}$ Novec^M Fluorosurfactant FC-4432, and another embodiment of the present invention relates to a method for imprint lithography that uses the imprinting material.